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TITLE: PARTICLE COLLECTING APPARATUS

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ABSTRACT:

PURPOSE: To perform analysis even at a place where the number of dusts are extremely few and to use a baffle plate having an arbitrary size, by providing plural stages of baffle plates each having a clean mirror surface in a main body in a state mounted to holding members in a detachable manner and allowing jet orifices having different diameters to communicate with plural states in

opposed relation to the baffle plates.

CONSTITUTION: When a silicon wafer 11 is used as each of baffle plates, by preliminarily matching the sizes of the recessed parts of each of holding members 12 with established wafer sizes, the silicon wafer 11 having an arbitrary size can be used as the baffle plate. When a pump is operated in use, the dust-containing gas sucked enters the first stage A1 of a collection apparatus 1 from a hose 2 and is sprayed onto the silicon wafer 11 from a nozzle 10 at a high speed to collect dust on the silicon wafer 11. A collected particle has a particle size of a definite value or more determined by the diameter of the nozzle and a particle having a particle size smaller than that of said particle is carried to the next stage A2 provided with a nozzle having a different diameter. Hereinafter, classification and collection are repeated in the same way and the dust not collected on the wafer of the final stage An is collected by a filter 5.

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